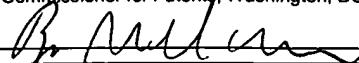
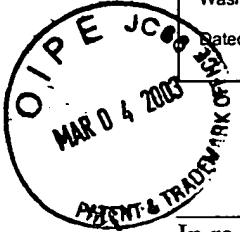




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AMENDMENT TRANSMITTAL LETTER				Docket No. 101361-0043	
Application No. 09/884,451-Conf. #1957	Filing Date June 19, 2001	Examiner J. Maldonado	Art Unit 2823		
Applicant(s): Robert P. Dolan, Bernhard F. Cordts, III, and Malvin Farley					
Invention: SIMOX USING CONTROLLED WATER VAPOR FOR OXYGEN IMPLANTS					
<b>TO THE COMMISSIONER FOR PATENTS</b>					
Transmitted herewith is an amendment in the above-identified application.					
The fee has been calculated and is transmitted as shown below.					
<b>CLAIMS AS AMENDED</b>					
	Claims Remaining After Amendment	Highest Number Previously Paid	Number Extra Claims Present	Rate	
<b>Total Claims</b>	13	- 20 =		x	0.00
<b>Independent Claims</b>	2	- 3 =		x	0.00
Multiple Dependent Claims (check if applicable) <input type="checkbox"/>					
Other fee (please specify):					
<b>TOTAL ADDITIONAL FEE FOR THIS AMENDMENT:</b> 0.00					
<input checked="" type="checkbox"/> Large Entity			<input type="checkbox"/> Small Entity		
<input type="checkbox"/> No additional fee is required for this amendment.					
<input type="checkbox"/> Please charge Deposit Account No. _____ in the amount of \$ _____ A duplicate copy of this sheet is enclosed.					
<input type="checkbox"/> A check in the amount of \$ _____ to cover the filing fee is enclosed.					
<input type="checkbox"/> Payment by credit card. Form PTO-2038 is attached.					
<input checked="" type="checkbox"/> The Commissioner is hereby authorized to charge and credit Deposit Account No. 141449 as described below. A duplicate copy of this sheet is enclosed.					
<input checked="" type="checkbox"/> Credit any overpayment.					
<input checked="" type="checkbox"/> Charge any additional filing or application processing fees required under 37 CFR 1.16 and 1.17.					
Dated: February 24, 2003					
 Reza Mollaaghbabu Attorney Reg. No.: 43,810					
NUTTER MCCLENNEN & FISH LLP World Trade Center West 155 Seaport Boulevard Boston, Massachusetts 02110-2699 617-439-2514					
<b>Amendment Transmittal</b> I hereby certify that this correspondence is being deposited with the U.S. Postal Service with sufficient postage as First Class Mail, in an envelope addressed to: Box Non-Fee Amendment, Commissioner for Patents, Washington, DC 20231, on the date shown below.					
Dated: February 24, 2003					
Signature:  (Reza Mollaaghbabu)					

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I hereby certify that this correspondence is being deposited with the U.S. Postal Service with sufficient postage as First Class Mail, in an envelope addressed to: Box Non-Fee Amendment, Commissioner for Patents, Washington, DC 20231, on the date shown below.

Dated: February 24, 2003

Signature:

(Reza Mollaaghataba)

# 11/B  
NE  
Ublawgj 3/16/03  
Docket No.: 101361-0043  
(PATENT)

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:  
Robert P. Dolan, et al

Application No.: 09/884,451

Group Art Unit: 2823

Filed: June 19, 2001

Examiner: Julio J. Maldonado

For: SIMOX USING CONTROLLED WATER  
VAPOR FOR OXYGEN IMPLANTS

### AMENDMENT AND RESPONSE UNDER 37 CFR 1.116

Box AF  
Commissioner for Patents  
Washington, DC 20231

Dear Sir:

In response to the Office Action mailed on December 13, 2002 from the United States Patent and Trademark Office in the above-referenced patent application, Applicants provide the following amendments and remarks. In addition to a marked-up copy of the amended claim in which additions are underlined and deletions are bracketed, a clean copy of all claims presently under examination is also provided.

Claims 1-19 are pending in the application. The Office Action considers claims 14-19, directed to a system for producing SIMOX wafers, presented as new claims in a response filed on October 3, 2003 to the previous Office Action, as being directed to a non-elected invention. Hence, only claims 1-13 have been subjected to examination in the present Office Action.

As discussed in more detail below, claims 1-13 are now believed to be in condition for allowance because none of the cited references teaches utilizing a fluid other than pure molecular oxygen as a *background* gas during an ion implantation step of a method of processing a silicon substrate to inhibit formation of threading dislocations in a top silicon layer formed in the

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